

FIG. 2

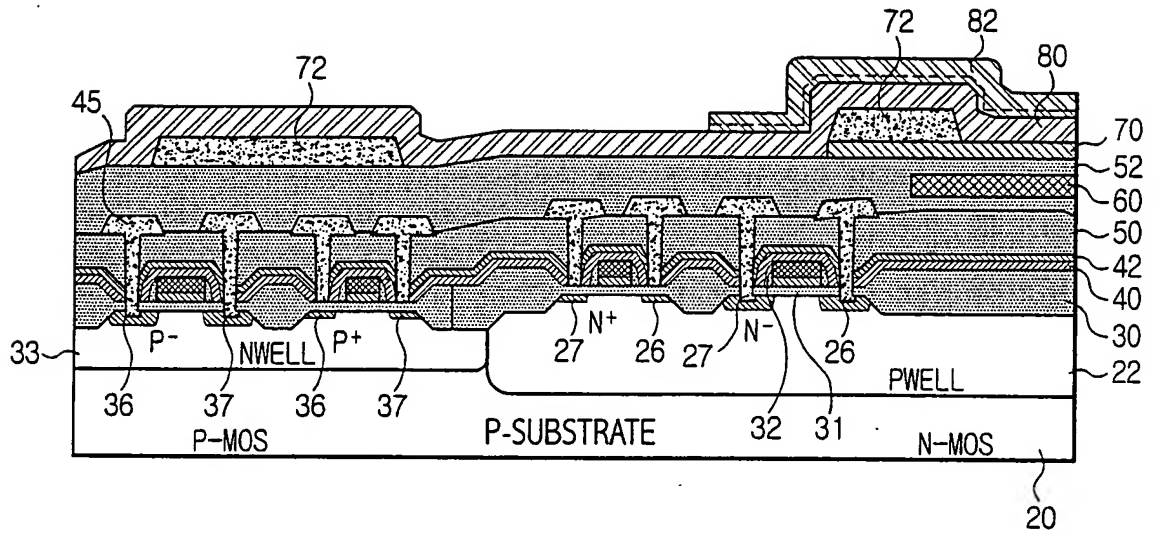


FIG. 3

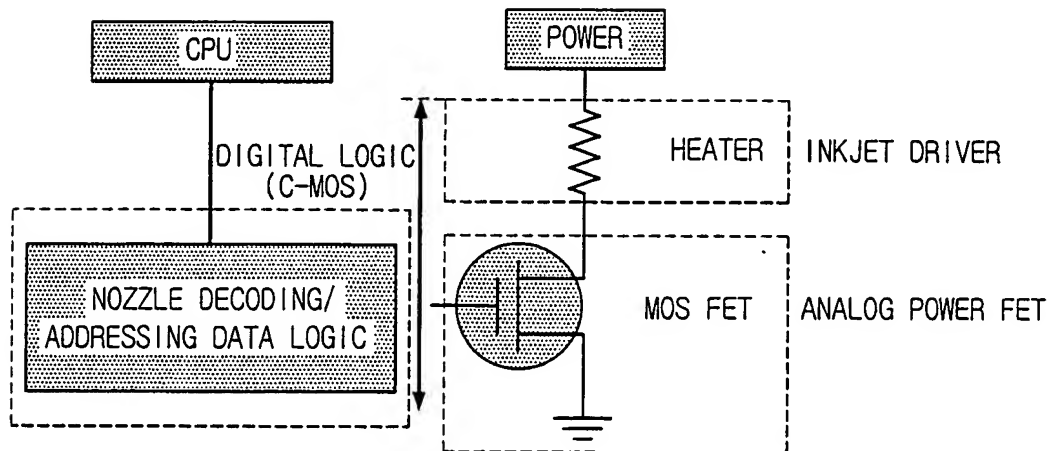


FIG. 4

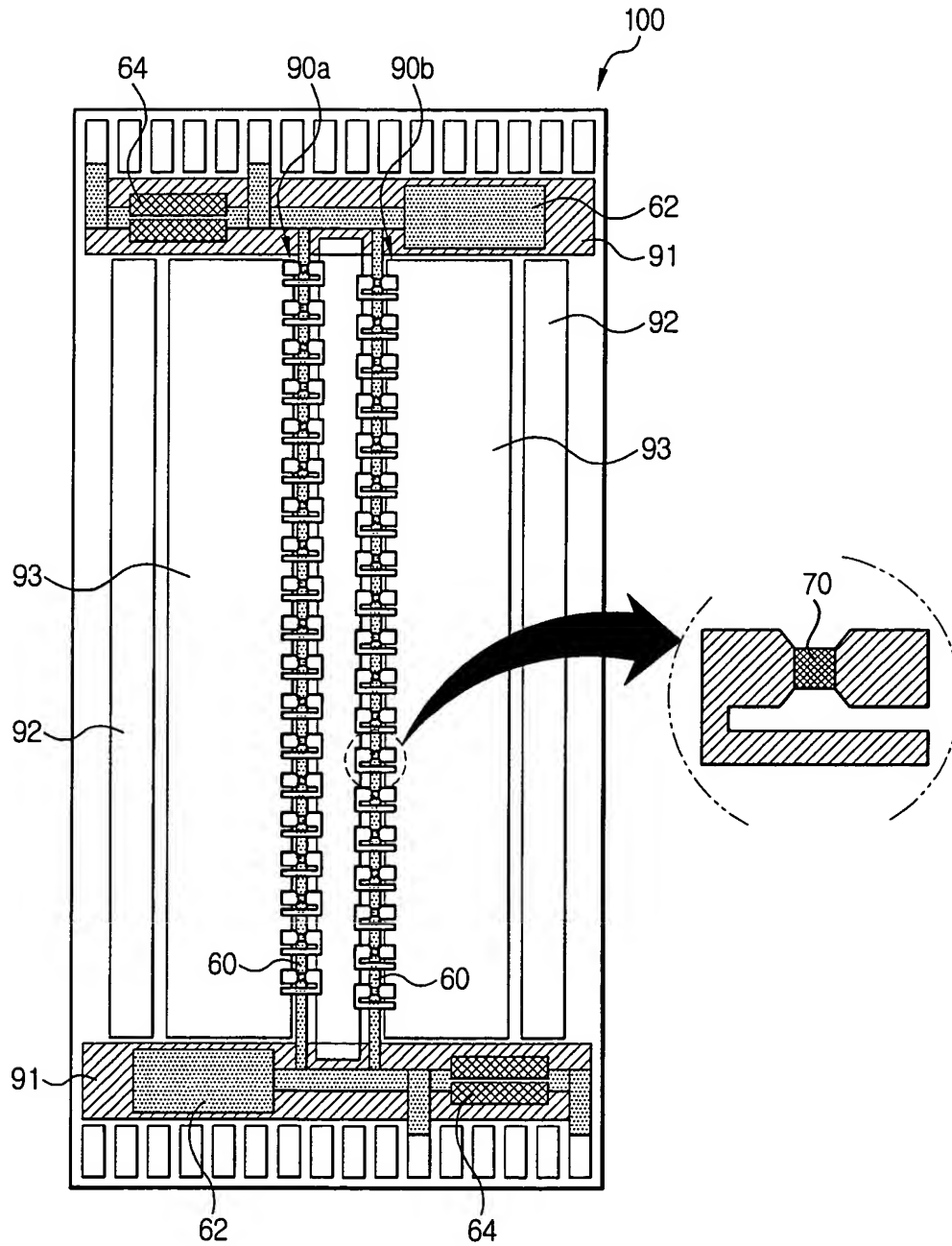


FIG. 5A

-Starting material (pwp18675) -Initial oxidation -1st SiN deposition

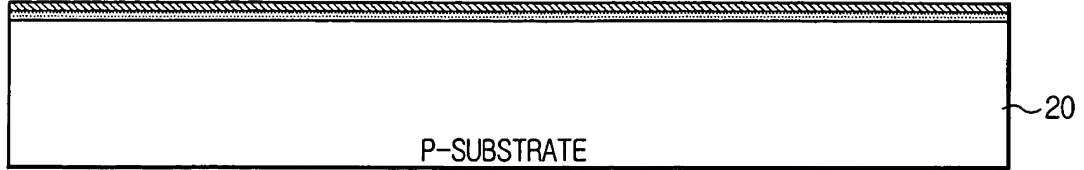


FIG. 5B

-PWELL photo -SiN etch -NEWLL implant

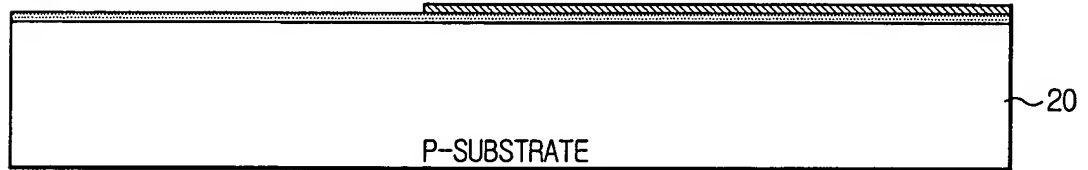


FIG. 5C

-NWELL oxidation SiN remove -PWELL implant -WDR (Well Drive In)

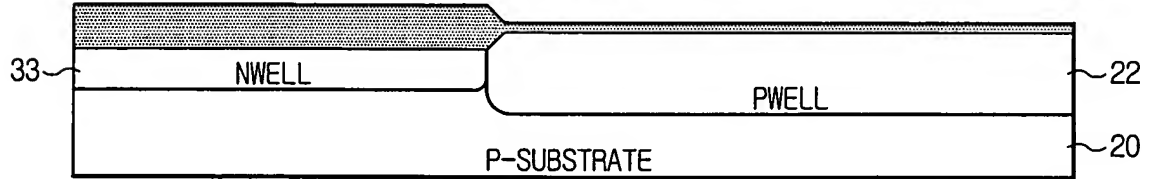


FIG. 5D

-Oxide remove -2nd oxidation -2nd SiN deposition

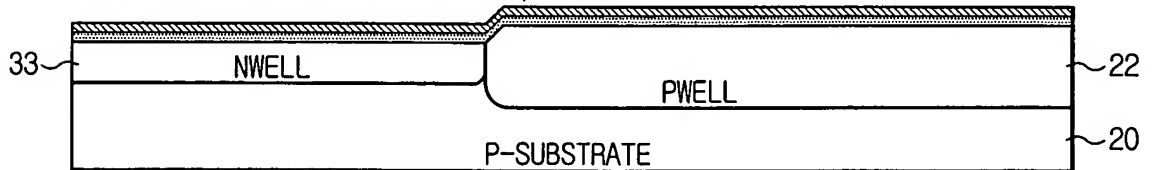


FIG. 5E

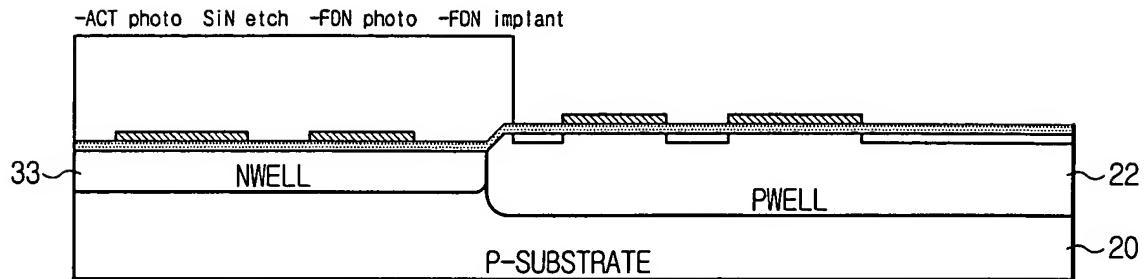


FIG. 5F

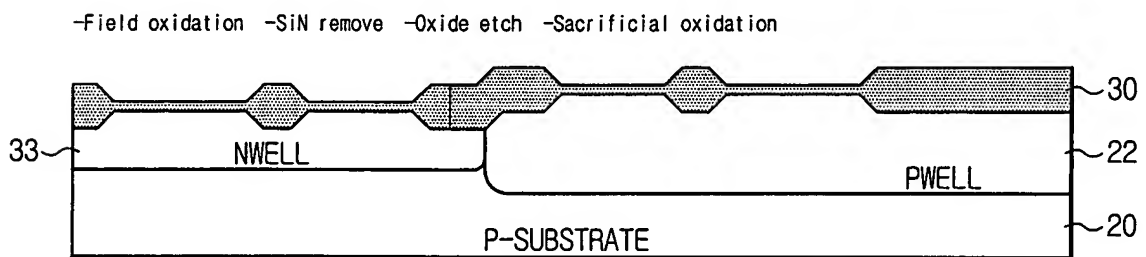


FIG. 5G

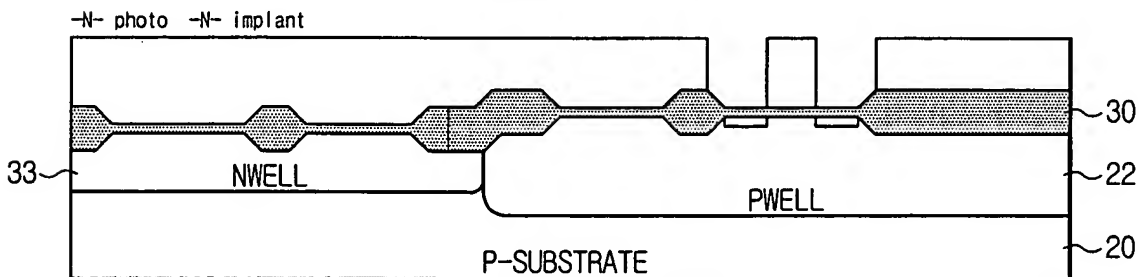


FIG. 5H

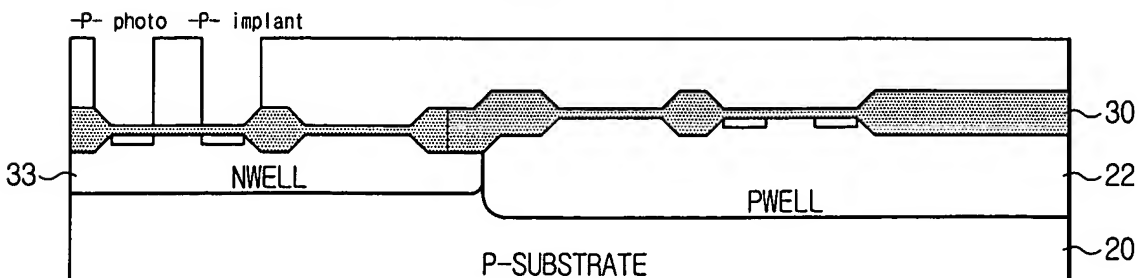


FIG. 5I

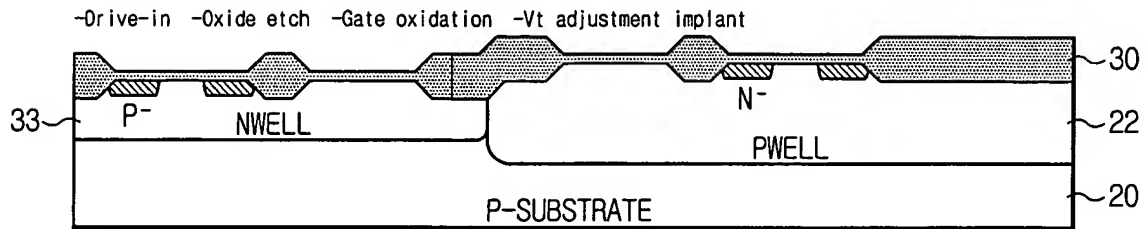


FIG. 5J

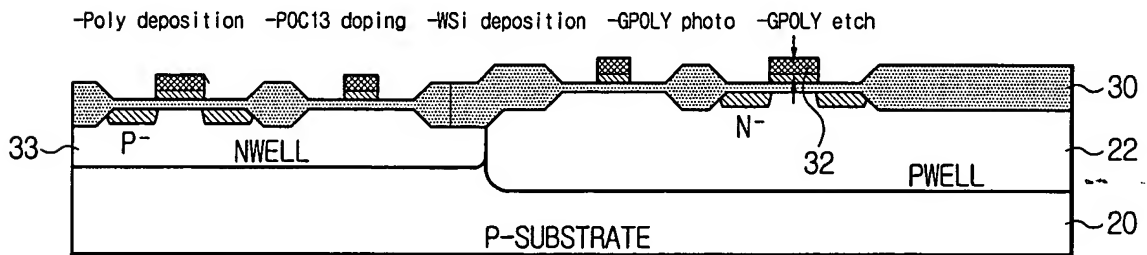


FIG. 5K

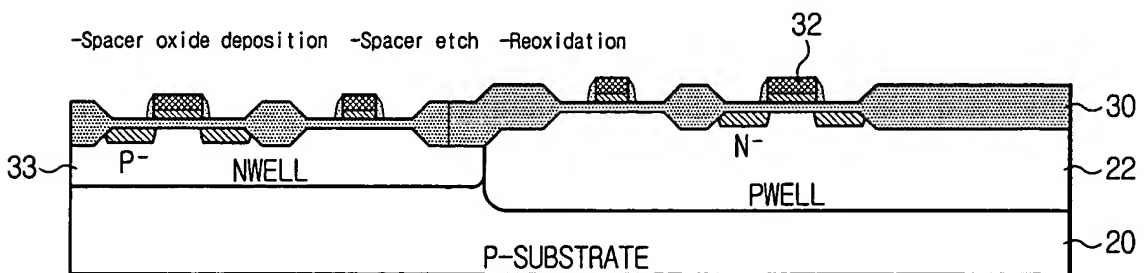


FIG. 5L

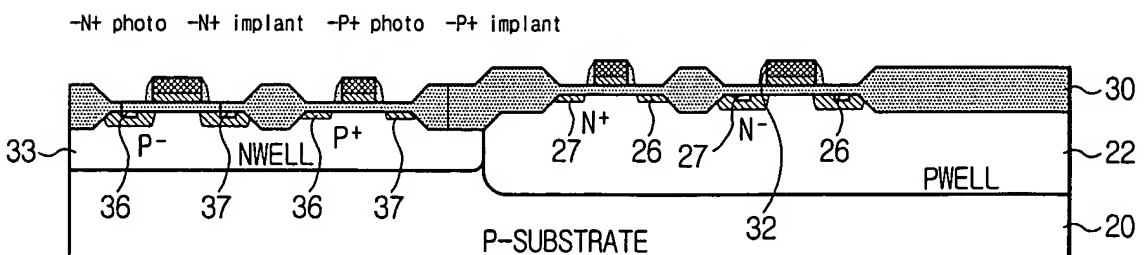


FIG. 5M

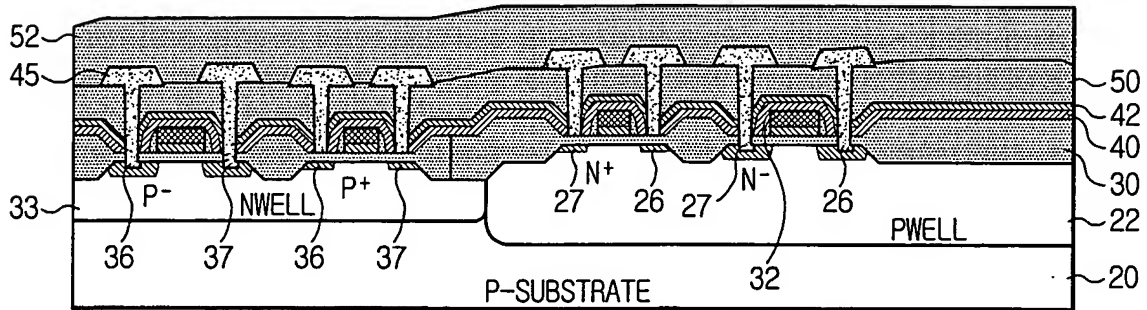


FIG. 5N

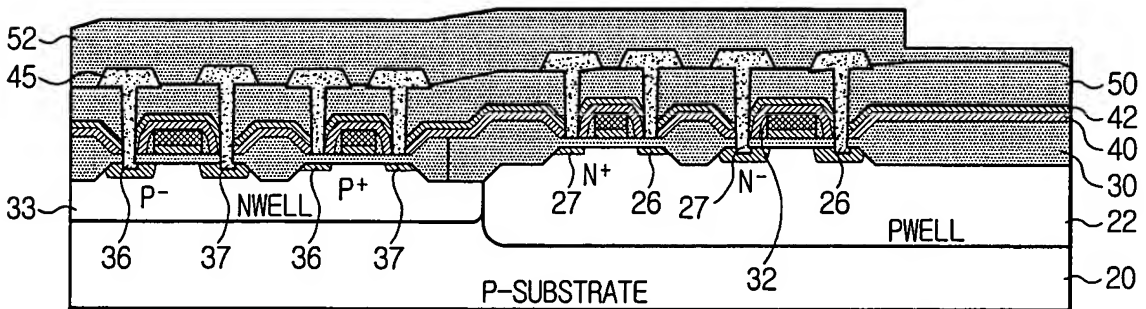


FIG. 5O

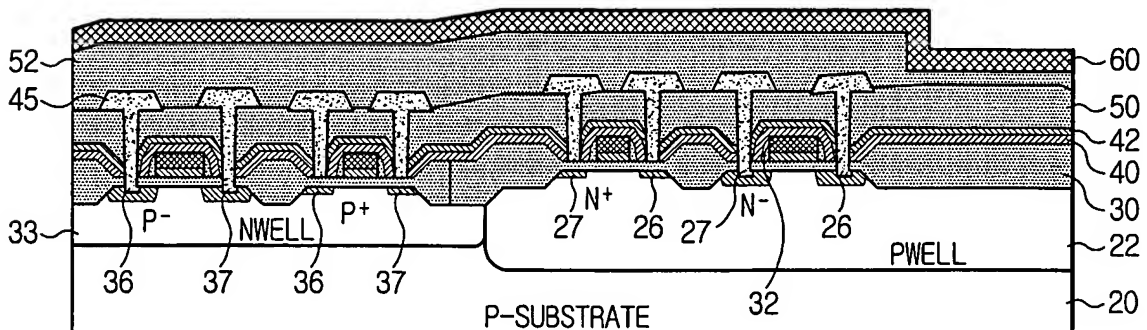


FIG. 5P

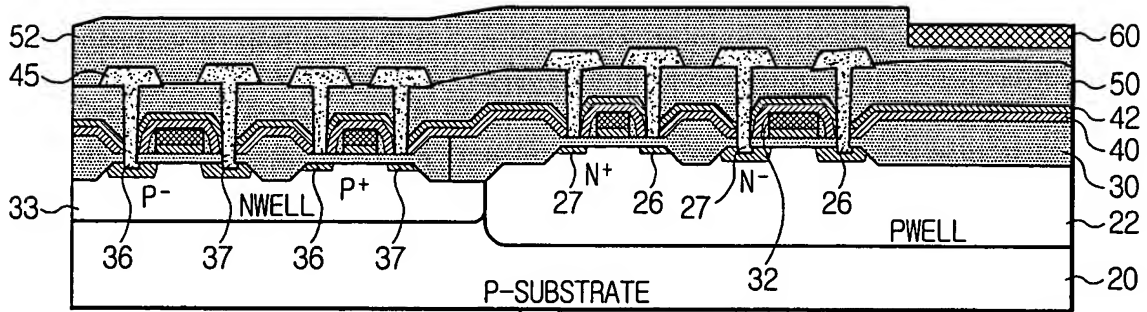


FIG. 5Q

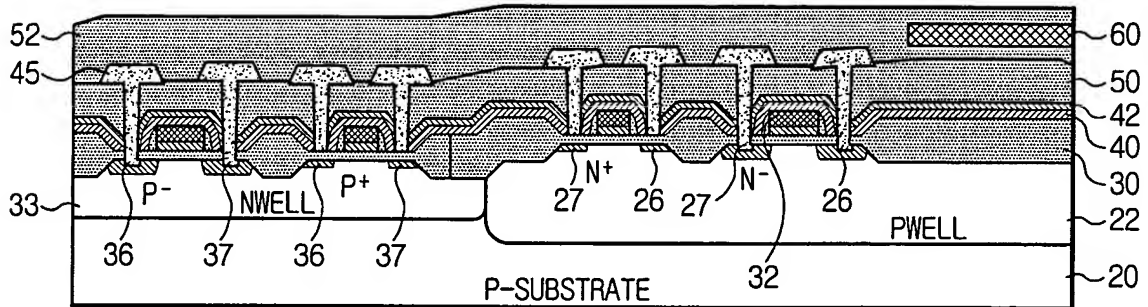


FIG. 5R

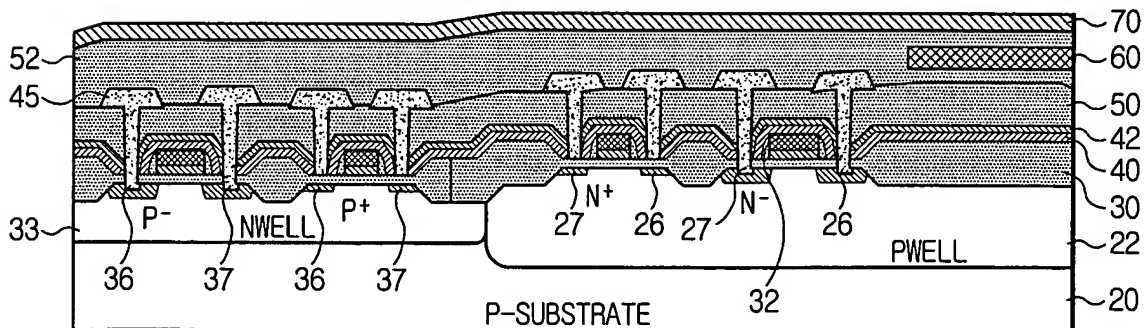




FIG. 5S

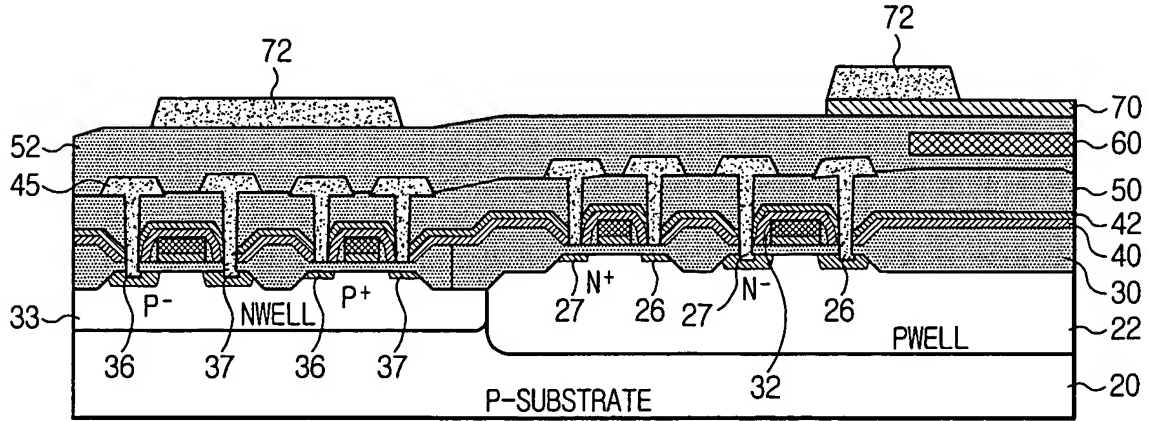


FIG. 5T

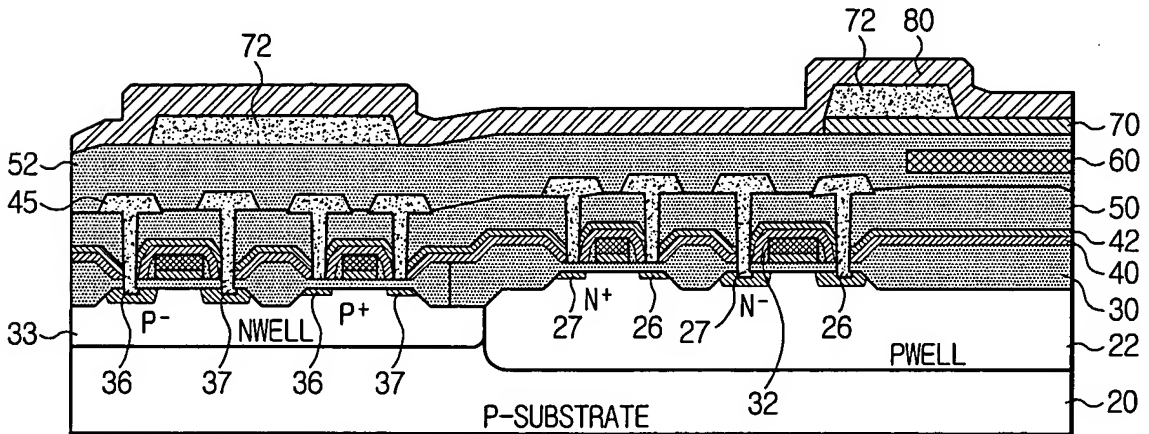


FIG. 5U

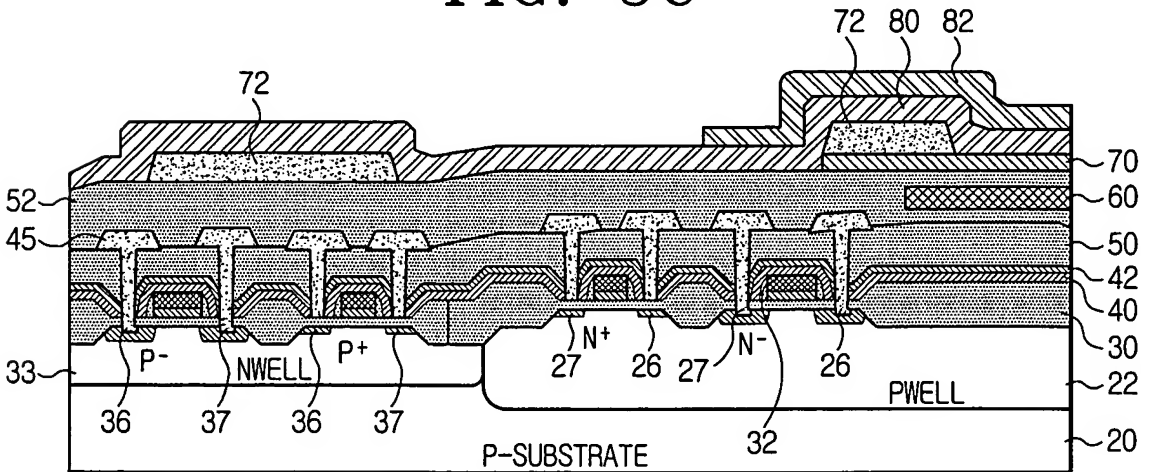


FIG. 6

